

METHOD OF CHARACTERIZING IMPLANTATION OF SPECIES IN A SUBSTRATE

ABSTRACT

A method for characterizing a dose or dosage of implanted atomic species in a substrate by annealing the substrate after implantation of the atomic species, with the anneal conducted at a temperature and for a time sufficient to cause the implanted atomic species to form blisters in a surface region of the substrate but below that which would cause a majority or significant amount of the blisters to burst; imaging the surface region of the substrate to obtain a surface image; and processing the surface image to characterize the implant dose of the atomic species. This characterization can be performed on a qualitative or quantitative basis, as desired.